EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4	"4411735".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/10 11:19
L2	22	("3700497" | "3871930" | "4039371").PN. OR ("4411735").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:20
L3	22	("3700497" | "3871930" | "4039371").PN. OR ("4411735").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:26
L4	1	"4411735".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:39
L5	1	"4740562".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:41
L6	19	"4740562"	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:42
L7	78	(wet etch$3 or wet-etch$3) near10 (water or "h.sub.2" or H2O) near10 (percent or "%")	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:44
L8	32	(wet etch$3 or wet-etch$3) near10 (anhydrous)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:55
L9	24	((wet etch$3 or wet-etch$3) near10 (anhydrous)) not (HF or hydroflouric)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:57
L10	0	((wet etch$3 or wet-etch$3) near10 (anhydrous)) near10 (hydroxide$1)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:58
L11	23	((wet etch$3 or wet-etch$3) near10 (water or "h.sub.2")) near10 (hydroxide$1) near10 (weight or "5" or percent$4)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 11:58
L12	23	((wet etch$3 or wet-etch$3) near10 (water or "h.sub.2")) near10 (hydroxide$1 or organic solvent) near10 (weight or "5" or percent$4)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 12:01
L13	14	((wet etch$3 or wet-etch$3) near10 (water or "h.sub.2")) near10 (hydroxide$1 or organic solvent) near10 (weight or "%" or percent$4)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 12:01

L14	24	((wet etch$3 or wet-etch$3) near10 (water or "h.sub.2")) near10 (hydroxide$1 or solvent or methanol or ethanol or ammonium) near10 (weight or "%" or percent$4)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:07
L15	1	"6849200".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:30
L16	1	"6284721".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:32
L17	2	(wet etch$3 or wet-etch$3) near10 ((water or "h.sub.2") adj 25%) near10 (hydroxide$1 or solvent or methanol or ethanol or ammonium)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:34
L18	0	(wet etch$3 or wet-etch$3) near10 (25% adj (water or "h.sub.2")) near10 (hydroxide$1 or solvent or methanol or ethanol or ammonium)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:35
L19	0	(wet etch$3 or wet-etch$3) near10 ("2"$1% adj (water or "h.sub.2")) near10 (hydroxide$1 or solvent or methanol or ethanol or ammonium)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:35
L20	0	(wet etch$3 or wet-etch$3) near10 (20% adj (water or "h.sub.2")) near10 (hydroxide$1 or solvent or methanol or ethanol or ammonium)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:36
L21	0	(wet etch$3 or wet-etch$3) near10 (10% adj (water or "h.sub.2")) near10 (hydroxide$1 or solvent or methanol or ethanol or ammonium)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:36
L22	3	(wet etch$3 or wet-etch$3) near10 (25% near3 (water or "h.sub.2")) near10 (hydroxide$1 or solvent or methanol or ethanol or ammonium)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:36
L23	9	("4465549" | "5064498" | "5071510" | "5086011" | "6168960" | "6352871").PN. OR ("6428718").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 13:38
L24	2950	develop$3 near10 solvent near10 (methanol or ethanol)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 14:36
L25	65	(("257".clas.) or ("438".clas.)) and develop$3 near10 solvent near10 (methanol or ethanol)	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 14:36
L26	9	(becker-gregory or gardner-geofrrey or harkness-brian). in.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 14:56

L27	9	(becker-gregory or gardner-geoffrey or harkness-brian). in.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/10 14:56
S1	2	"20060286809"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:38
S2	219	((organopolysiloxane or organo-polysiloxane) near10 average near10 silicon near10 alkenyl)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:51
S3	1556	((organosilicon or organo-silicon) near10 hydrogen)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:51
S4	5272	(catal$4 near10 (hydrosilylation or hydro-silylation))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:52
S5	258469	(solvent near10 (alcohol or monoether or diether or aprotic))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:55
S6	100049	(base near10 hydroxide)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:55
S7	47	(solvent near10 anol)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:56
S8	246656	(solvent near10 (methanol or ethanol or propanol or isopropanol or butanol))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:56
S9	1407186	(rework or clean$3)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:57
S10	1	S2 and S3 and S4 and S5 and S6 and S8 and (negative near10 (photoresist or photo-resist or photo resist or resist)) and (heat$3 or bak$3) and radiat$3	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 08:59

S11	26503	organopolysiloxane	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:09
S12	22624	organosilicon	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:10
S13	1	S11 and S12 and S4 and S5 and S6 and S8 and (negative near10 (photoresist or photo-resist or photo resist or resist)) and (heat$3 or bak $3) and radiat$3	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:11
S14	0	organopolysiloxane same organosilicon same hydrosilylat$4 same (heat$3 or bak$3) same (etch$3)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:12
S15	4	"549691".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:32
S16	2	"5496961".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:32
S17	1	"5591622".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:36
S18	2	"4585836".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:37
S19	2	"4584355".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:37
S20	2	"4530879".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:37

S21	2	"4510094".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:38
S22	2	"20020158317"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 09:39
S24	1	"6617674".pn.	USPAT	ADJ	ON	2008/03/06 09:46
S31	2	2002/0094671	USPAT	ADJ	ON	2008/03/06 09:49
S32	34	("20020094671" | "4610079" | "4670088" | "5143865" | "5496775" | "5554887" | "5703406" | "5824569" | "5834843" | "5844779" | "5867417" | "5908317" | "5933713" | "5950070" | "5969426" | "5977641" | "6020629" | "6054772" | "6077380" | "6097098" | "6107164" | "6137164" | "6150717" | "6153448" | "6181569" | "6208018" | "6297553" | "6331450" | "6368896" | "6379999" | "6499216" | "6531341" | "6780747" | "6900074").PN. OR ("7183191").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:49
S33	3	2003/0027373	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:50
S34	3	2002/0115236	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:51
S35	2	2002/0094671	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:51
S36	7	2002/0063332	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:52
S37	1	"6433440".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:53
S38	1	"5685885".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:54
S39	1	"5678301".pn.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/03/06 09:54
S40	0	(negative near10 (photoresist or photo-resist or photo resist or resist)) same (organopolysiloxane) same (organosilicon) same (hydrosilylat$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 10:03

S41	0	(photoresist or photo-resist or photo resist or resist) same (organopolysiloxane) same (organosilicon) same (hydrosilylat$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 10:04
S42	111	(organopolysiloxane) same (organosilicon) same (hydrosilylat$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 10:05
S43	9	("257".clas. or "438".clas.) and (organopolysiloxane) same (organosilicon) same (hydrosilylat$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 10:05
S44	3	"6810585".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 10:06
S45	0	("2003/0214051").URPN.	USPAT	ADJ	ON	2008/03/06 10:08
S46	2	"1041117"	USPAT	ADJ	ON	2008/03/06 10:21
S47	1	"6239378".pn.	USPAT	ADJ	ON	2008/03/06 10:22
S48	1	"6083774".pn.	USPAT	ADJ	ON	2008/03/06 10:22
S49	1	"6369185".pn.	USPAT	ADJ	ON	2008/03/06 10:24
S50	202	((negative) near10 (photoresist or resist or photo resist or photo-resist)) same (UV or ultraviolet or violet or radiat$4 or irrdiat$4) same (heat$3 or bak$3) same (develop$3) same (etch$3)	USPAT	ADJ	ON	2008/03/06 11:31
S51	7615050	(@pd< "20030728" or @ad< "20030728")	USPAT	ADJ	ON	2008/03/06 11:34
S52	180	S50 and S51	USPAT	ADJ	ON	2008/03/06 11:35
S53	69	((("257".clas.) or ("438".clas.)) and S52	USPAT	ADJ	ON	2008/03/06 11:37

S54	0	(((negative) near10 (photoresist or resist or photo resist or photo-resist)) same (UV or ultraviolet or violet or radiat$4 or irrdiat$4) same (heat$3 or bak$3) same (develop$3 near20 (methanol or propanol or butanol)) same (etch$3 near20 (alcohol or monoether or diether or aprotic) near20 (hydroxide $1)))	USPAT	ADJ	ON	2008/03/06 11:43
S55	1	(((negative) near10 (photoresist or resist or photo resist or photo-resist)) and (UV or ultraviolet or violet or radiat$4 or irrdiat$4) and (heat$3 or bak$3) and (develop$3 near20 (methanol or propanol or butanol)) and (etch$3 near20 (alcohol or monoether or diether or aprotic) near20 (hydroxide $1)))	USPAT	ADJ	ON	2008/03/06 11:45
S56	28317	(negative) near10 (photoresist or resist or photo resist or photo-resist)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 11:49
S57	578562	(UV or ultraviolet or violet or radiat$4 or irrdiat$4)	USPAT	ADJ	ON	2008/03/06 11:50
S58	1461595	(heat$3 or bak$3)	USPAT	ADJ	ON	2008/03/06 11:50
S59	8989	(develop$3 near20 (methanol or propanol or butanol))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 11:51
S60	360	(etch$3 near20 (alcohol or monoether or diether or aprotic) near20 (hydroxide $1))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 11:51
S61	0	(etch$3 near20 (alcohol or monoether or diether or aprotic) near20 (hydroxide$1) near20 phosphazene)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 11:53
S62	1	S56 and S57 and S58 and S59 and S60	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 11:54

S63	19929	(develop$3 near20 (alcohol or methanol or propanol or butanol))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:11
S64	360	(etch$3 near20 (alcohol or monoether or diether or aprotic) near20 (hydroxide$1 or phosphazene))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:12
S65	3	S56 and S57 and S58 and S63 and S64	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:13
S66	11111	(develop$3 near20 (methanol or propanol or butanol or ethanol))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:26
S67	21758	(develop$3 near20 (methanol or propanol or butanol or ethanol or alcohol))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:27
S68	3	S56 and S57 and S58 and S67 and S64	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:28
S69	96	S56 and S57 and S58 and develop$3 and etch$3 and rework$3	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:34
S70	87	S51 and S69	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:34
S71	383	((negative) near10 (photoresist or resist or photo resist or photo-resist)) same (UV or ultraviolet or violet or radiat$4 or irrdiat$4) same (heat$3 or bak$3) same (develop$3) same (etch$3)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:37
S72	0	((negative) near10 (photoresist or resist or photo resist or photo-resist)) same (UV or ultraviolet or violet or radiat$4 or irrdiat$4) same (heat$3 or bak$3) same (develop$3) same (etch$3) same rework$3	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:38

S73	0	((negative) near10 (photoresist or resist or photo resist or photo-resist)) same (UV or ultraviolet or violet or radiat$4 or irrdiat$4) same (heat$3 or bak$3) same (develop$3) same (etch$3) same rework	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:38
S74	157	((negative) near10 (photoresist or resist or photo resist or photo-resist)) same (UV or ultraviolet or violet or radiat$4 or irrdiat$4) same (heat$3 or bak$3) same (develop$3) same (etch$3) same (additional or subsequent or multiple or second)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:39
S75	71	S74 and S51	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/06 13:42
S76	22	(("257".clas.) or ("438".clas.)) and S75	USPAT	ADJ	ON	2008/03/06 13:43
S77	755	(remov$3 or etch$3 or develop$5) near10 (organic solvent) near10 (base)	USPAT	ADJ	ON	2008/03/06 16:30
S78	10	(remov$3 or etch$3 or develop$5) near20 ((organic solvent) near10 (alcohol or monoether or diether or aprotic or polar)) near20 ((base) near10 (ammoni$4 or hydroxide$1 or phosphazene))	USPAT	ADJ	ON	2008/03/06 16:34
S79	18	(remov$3 or etch$3 or develop$5) near20 ((organic solvent) near10 (methanol or ethanol)) near20 ((base) near10 (ammoni$4 or hydroxide$1 or phosphazene))	USPAT	ADJ	ON	2008/03/06 16:57
S80	14	S79 not S78	USPAT	ADJ	ON	2008/03/06 16:57
S81	0	(remov$3 or etch$3 or develop$5) near20 ((organic solvent) near10 (methanol or ethanol)) near20 ((base) near10 (ammonium hydroxide))	USPAT	ADJ	ON	2008/03/06 17:16
S82	180	((base) near10 ((ammonium hydroxide$1 near5 tretra) or phosphazene))	USPAT	ADJ	ON	2008/03/06 17:23

S83	1	("257".clas. or "438".clas.) and ((base) near10 ((ammonium hydroxide$1 near5 tretra) or phosphazene))	USPAT	ADJ	ON	2008/03/06 17:24
S84	27	((base) near10 ((ammonium hydroxide$1 near5 tretra) or phosphazene)) same (etch$3 or remov$3 or develop$3)	USPAT	ADJ	ON	2008/03/06 17:24
S85	26	S84 and S51	USPAT	ADJ	ON	2008/03/06 17:25
S86	2	"6362116".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:12
S87	2	"5856065".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:12
S88	2	"5470693".pn.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:22
S89	8285	develop$3 near10 (methanol or ethanol)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:25
S90	14987032	(@pd<"19900728" or @ad<"19900728")	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:25
S91	3077	S89 and S90	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:26
S92	4238343	(@pd<"19700728" or @ad<"19700728")	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:26
S93	62	S89 and S92	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/03/08 16:26

| S94 | 135 | ("257".clas. or "438".clas.) and S89 | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/03/08 16:27 |

3/10/2008 2:58:54 PM
C:\Documents and Settings\hhung\My Documents\EAST\Workspaces\10565036.wsp